

### TUTORIAL 3

- Explain briefly the charge condition for N and P materials at room temperature.
  - Why is there a majority carrier flow when the N and P materials are adjacent to each other?
  - Why is the flow of the majority carriers not continuous until all of the carriers are recombined?

Draw suitable diagrams to assist you in providing the explanation.

- Calculate the ratio of the current flowing through a p-n junction when the junction is forward biased by a 0.05 V, to the current flowing through the same junction when it is reverse biased by a voltage of the same magnitude at 300°K.
  - Calculate the voltage that will generate a reverse current equivalent to 90% of its saturated value at 300°K in a Germanium diode p-n junction.
- Draw and describe briefly on the energy band structure of an open circuit p-n junction.
- A 1 mA forward current was generated at 300°K when a voltage  $V_1$  was supplied across a Silicon p-n junction diode having the following parameters:

$$\text{Donor density, } N_D = 10^{16} \text{ cm}^{-3}$$

$$\text{Acceptor density, } N_A = 5 \times 10^{18} \text{ cm}^{-3}$$

$$\text{Average lifetime, } \tau_n = \tau_p = 1 \text{ } \mu\text{s}$$

$$\text{Cross-section area, } A = 0.01 \text{ cm}^2$$

$$\text{Electron mobility in P material, } \mu_n = 120 \text{ cm}^2/\text{Vs}$$

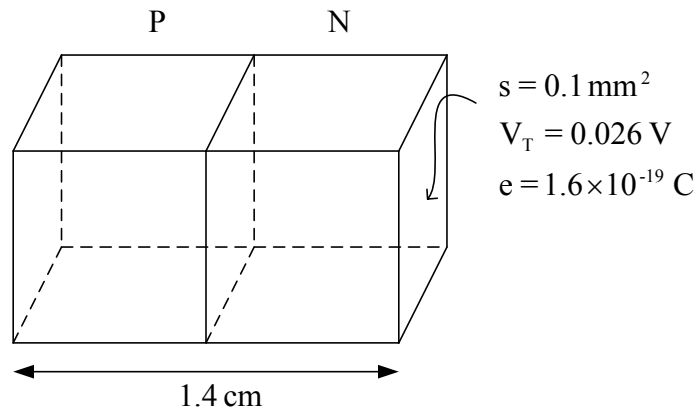
$$\text{Hole mobility in N material, } \mu_p = 1100 \text{ cm}^2/\text{Vs}$$

Calculate  $V_1$  when the length of the materials P and N are much larger than the minority carrier diffusion length. Given:  $n_i = 1.5 \times 10^{10} \text{ cm}^{-3}$  and  $V_T = 26 \text{ mV}$  at 300°K.

- In a p-n material, conductivity of the P material is  $1/\Omega\text{cm}$ . The conductivity of the N material is  $0.1/\Omega\text{cm}$ . The acceptor impurity concentration in the P material is  $5 \times 10^{22}/\text{cm}^3$ . Determine the reverse saturated current at 300°K if the material's cross-section area is  $4 \text{ mm}^2$ . Given  $N_D = 1 \times 10^{22}/\text{cm}^3$  and  $n_i = 5 \times 10^{16}/\text{m}^3$ .

Note: Mobility of electron,  $\mu_n = e\tau_n/m$ , and mobility of hole,  $\mu_p = e\tau_p/m$ , where  $\tau_n$  and  $\tau_p$  is the lifetime of the electron in the P material and hole in the N material, respectively.  $m$  is the electron mass.

6. A Silicon p-n diode is shown by the following diagram. The length of P is equivalent to the length of N. The diode has  $N_A = N_D = 10^{22}$  atoms/m<sup>3</sup> and the majority carrier lifetime is 100  $\mu$ s in each P and N. Resistivity in the P material is  $1.3 \times 10^{-3}$   $\Omega$ m and the resistivity in the N material is  $4.6 \times 10^{-3}$   $\Omega$ m at room temperature. Resistance of the intrinsic Silicon material is 5.5 M $\Omega$ . Electron mobility in N and hole mobility in P is 1/3 of the electron and hole mobility in the intrinsic material, respectively. Calculate the saturated current at room temperature.



7. A Si p-n junction is formed by a P material with  $1.3 \times 10^{-3}$   $\Omega$ m resistivity and an N material with  $4.6 \times 10^{-3}$   $\Omega$ m resistivity at room temperature (293°K). The lifetime for the minority carriers in P and N is 100  $\mu$ s and 150  $\mu$ s, respectively. The junction area is 1 mm<sup>2</sup>. If  $\mu_p = 4.8 \times 10^{-2}$  m<sup>2</sup>/Vs,  $\mu_n = 0.135$  m<sup>2</sup>/Vs and  $n_i = 6.5 \times 10^{16}$ /m<sup>3</sup>, calculate the reverse bias saturated current with the assumption that the P and N regions are much longer than the diffusion length.

Note:  $p_n = n_i^2 / n_n$  and  $n_p = n_i^2 / p_p$